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states:(71) Applicant: NIPPON TELEGR &  
<NTT>(72) Inventor: OMACHI TOKURO  
KADOTA YOSHIKI  
OKAMOTO HIROSHI  
WATANABE YOSHIO

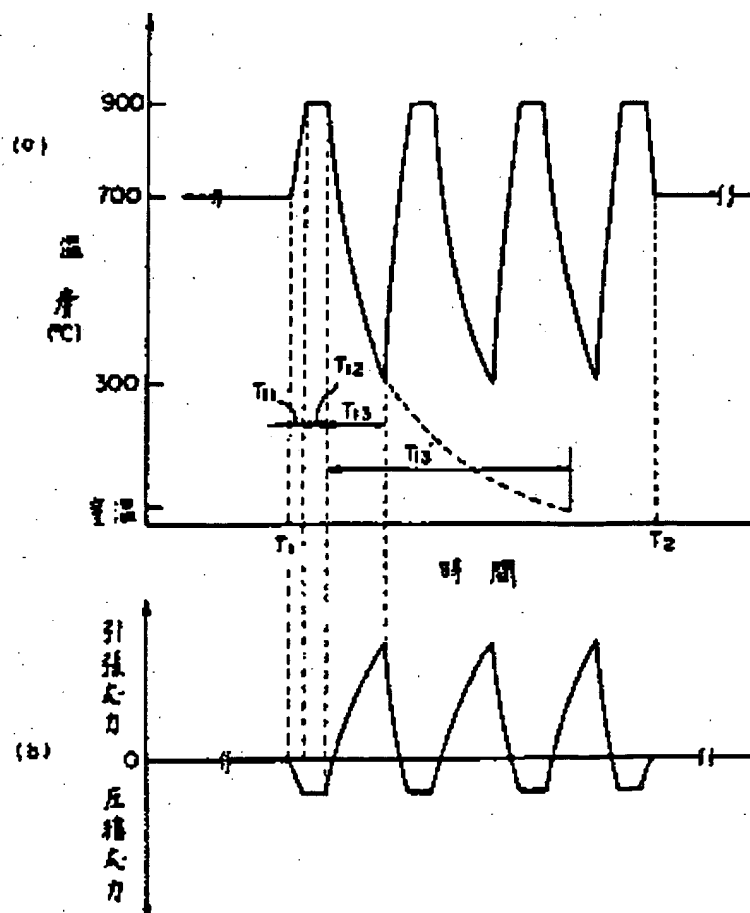
(74) Representative:

(54) HEAT TREATMENT  
METHOD

(57) Abstract:

**PURPOSE:** To effectively accomplish the decrease in dislocation of a defect in a short period by a method wherein the epitaxially grown layer of a III-V compound semiconductor is formed on an Si substrate, and a heat treatment process at a specific temperature and for a specific period is repeated at least once.

**CONSTITUTION:** A GaAs layer is epitaxially grown on an Si substrate by conducting an organic metal vapor-growth method at about 700°C for the time T1=45minutes. The film thickness of the above-mentioned layer is set at 1.5μm for improvement of crystallizability by heat treatment. Then, temperature is raised to 900°C in the period of time T11=3minutes, said temperature is maintained for T11=5minutes, and the cooled down to 300°C in T13=12minutes. T13=50minutes are required using



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## JP1246818A2: HEAT TREATMENT METHOD

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Country: **JP Japan**

Kind:

 Inventor(s): **OMACHI TOKURO  
KADOTA YOSHIKI  
OKAMOTO HIROSHI  
WATANABE YOSHIO**

 Applicant(s): **NIPPON TELEGR & TELEPH CORP <NTT>**  
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Abstract: **Purpose:** To effectively accomplish the decrease in dislocation of a defect in a short period by a method wherein the epitaxially grown layer of a III-V compound semiconductor is formed on an Si substrate, and a heat treatment process at a specific temperature and for a specific period is repeated at least once.

**Constitution:** A GaAs layer is epitaxially grown on an Si substrate by conducting an organic metal vapor-growth method at about 700°C for the time T1=45minutes. The film thickness of the above-mentioned layer is set at 1.5μm for improvement of crystallizability by heat treatment. Then, temperature is raised to 900°C in the period of time T11=3minutes, said temperature is maintained for T11=5minutes, and the cooled down to 300°C in T13=12minutes. T13=50minutes are required using the method heretofore in use, and the cooling period of time is sharply reduced. The above-mentioned cycle is repeated four times, and the heat treatment for decreasing crystal dislocation is completed. Besides, a GaAs device layer of 1.5μm in thickness is epitaxially grown in the period of time T3=45minutes, and an excellent thin film crystal of 3μm in total thickness is obtained.

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